

Thick Mesostructured Films *via* Light Induced Self-Assembly

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ELECTRONIC SUPPORTING INFORMATION

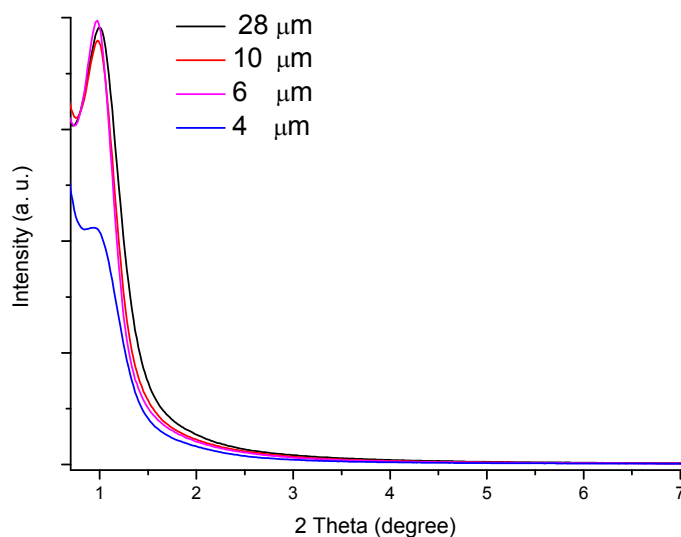


Figure S1. XRD patterns obtained for calcined sample of P123/PDMOS = 0.75 of various initial film thickness: (—) 4 μm, (—) 6 μm, (—) 10 μm and (—) 28 μm